



제 30회 한국반도체학술대회

The 30th Korean Conference on Semiconductors

2023년 2월 13일(월)~ 15일(수) | 강원도 하이원리조트(그랜드호텔 컨벤션타워)

2023년 2월 15일(수), 10:45-12:30

Room B (에메랄드 II+III, 5층)

D. Thin Film Process Technology 분과

[WB2-D] Thin Films Transistors II

좌장: 백인환 교수(인하대학교), 안지훈 교수(한양대학교)

<p>WB2-D-1 10:45-11:15 [초청]</p>	<p>Atomic Layer Deposition for Emerging Semiconducting Materials In-Hwan Baek¹ and Seong Keun Kim^{2,3} <i>¹Department of Chemical Engineering, Inha University, ²Electronic Materials Research Center, KIST, ³KU-KIST Graduate School of Converging Science and Technology, Korea University</i></p>
<p>WB2-D-2 11:15-11:30</p>	<p>Influence of HfO₂-Based Gate Stack on the Performance of P-channel SnO Thin Film Transistor Fabricated by Atomic Layer Deposition Jina Kim¹, Hee Won Jang¹, Myeong Gil Chae¹, Bo Keun Park², Taek-Mo Chung², and Jeong Hwan Han¹ <i>¹Department of Materials Science and Engineering, Seoul National University of Science and Technology, ²Division of Advanced Materials, KRICT</i></p>
<p>WB2-D-3 11:30-11:45</p>	<p>Two-Dimensional Tin Sulfide Compounds Deposited by Atomic Layer Deposition Using a Novel Tin Precursor Dong Geun Kim, Jeong-Hun Choi, Ji-Min Lee, and Ji-Hoon Ahn <i>Department of Materials Science and Chemical Engineering, Hanyang University</i></p>
<p>WB2-D-4 11:45-12:00</p>	<p>Performance Enhancement of Transparent p-type Copper Oxide Thin Film Transistors with Alkali Metal Doping Seokhyeon Baek, Wonsik Kim, Taehyun Kwak, and Sungjun Park <i>Department of Electrical and Computer Engineering, Ajou University</i></p>
<p>WB2-D-5 12:00-12:15</p>	<p>Low-temperature Growth of 2D-MoS₂ Thin Films by Plasma-enhanced Atomic Layer Deposition Using New Molybdenum Precursor Jeong-Hun Choi, Dong Geun Kim, Min-Ji Ha, Ji-Min Lee, and Ji-Hoon Ahn <i>Department of Materials Science and Chemical Engineering, Hanyang University</i></p>
<p>WB2-D-6 12:15-12:30</p>	<p>ALD Supercycle에 따른 다층 구조 ZnO/SnO₂ 박막 트랜지스터의 성능 향상에 대한 연구 박찬영, 이세형, 박소영, 백동기, 이문석 <i>부산대학교 전기전자공학과</i></p>